

Title (en)
POSITIVE PHOTORESIST COMPOSITIONS

Publication
EP 0200129 B1 19920205 (DE)

Application
EP 86105450 A 19860419

Priority
DE 3515693 A 19850502

Abstract (en)
[origin: EP0200129A2] Scattered radiation and halation effects can be effectively suppressed in positive photoresist coatings, especially when they are applied to highly reflective substrates by adding compounds of the general formula I <IMAGE> where R<1> to R<4> denote, in each case, hydroxyl or C1-6-alkoxy and R<5> to R<10> denote, in each case, hydrogen or C1-6-alkyl, to photoresist compositions with a diazoquinone/novolak base.

IPC 1-7
G03F 7/022; **G03F 7/09**

IPC 8 full level
G03F 7/022 (2006.01); **G03F 7/09** (2006.01)

CPC (source: EP)
G03F 7/0226 (2013.01); **G03F 7/091** (2013.01)

Cited by
EP0298393A3; EP0287750A3; US4818658A

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DOCDB simple family (publication)
EP 0200129 A2 19861105; **EP 0200129 A3 19871104**; **EP 0200129 B1 19920205**; AT E72488 T1 19920215; DE 3515693 A1 19861106; DE 3683794 D1 19920319

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